

Wafer Cleaning Procedure

1. Pre-Cleaning Instructions

- 1.1. Double glove before all cleaning processes.
- 1.2. Capture all solvent waste into the solvent waste jug in the solvent hood.
- 1.3. Refill an acetone and isopropanol (IPA) squirt bottle prior to cleaning.

2. Tweezer Cleaning

- 2.1. Rinse the tweezer with de-ionized (DI) water over the sink.
- 2.2. Inspect tweezer for foreign material.
- 2.3. Remove any foreign material with acetone and a swab or wipe.
- 2.4. Rinse the tweezer with acetone into the solvent waste jug.
- 2.5. Rinse the tweezer with IPA into the solvent waste jug.
- 2.6. Place a 4x4 polyester wipe on top of a 4x4 cellulose wipe on the solvent hood bench.
- 2.7. Blow dry the tweezers with nitrogen, using the polyester wipe to absorb any IPA coming off the tweezers.

3. Wafer Cleaning

- 3.1. Place a 4x4 polyester wipe on top of a 4x4 cellulose wipe in the solvent hood.
- 3.2. Using a wafer tweezer, pickup the wafer on the wafer flat.
- 3.3. Rinse the entire wafer with de-ionized (DI) water over the sink.
- 3.4. Rinse the entire wafer with acetone into the solvent waste jug.
- 3.5. Rinse the entire wafer with IPA into the solvent waste jug.
- 3.6. Blow dry the wafer with nitrogen, starting from the top of wafer and going down, using the polyester wipe to absorb any IPA coming off the wafer.